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Date Submitted: 1/7/05

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1 of 7 Sheet

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Application Number	10/784,586				
Filing Date	02/23/2004				
First Named Inventor	Harry A. ATWATER et al.				
Group Art Unit	1764				
Examiner Name	Unassigned				
Attorney Docket Number	047071-0109				

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<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	INFORMAT	ION DISCLO	SURE	Application Number	10/784,586	
	STATEMEN	IT BY APPLI	CANT	Filing Date	02/23/2004	
	Data Su	bmitted: 1/7/	'05	First Named Inventor	Harry A. ATWATER et al.	
	Date Su	Difficed. 1777	US	Group Art Unit	1764	
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Sheet	2	of	7	Attorney Docket Number	047071-0109	

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		Number	Kind Code <sup>2</sup> (if known)						
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	Date Sub	milled: 1777	05	Group Art Unit	1764		
	(use as many si	heets as ne	cessary)	Examiner Name	Unassigned		
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				U.S. PATENT DOCUMENTS	<b>;</b>	
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<sup>&</sup>lt;sup>1</sup> Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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	Date Sub	mitted: 1/7/	US	Group Art Unit	1764	
	(use as many si	heets as ne	cessary)	Examiner Name	Unassigned	
Sheet	4	of	7	Attorney Docket Number	047071-0109	

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Examiner Initials*	<u></u>	U.S. Patent	Document	Name of Patentee or Applicant of Cited Document	Date of Publication of	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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Examiner Initials*	Cite No.1	For Office <sup>3</sup>	eign Patent D Number <sup>4</sup>	ocument Kind Code <sup>5</sup> (if known)	Name of Patentee or Applicant of Cited Documents	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
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	miner als*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.				
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	INFORMATIO	N DISCLO	SURE	Application Number	10/784,586	-	
	STATEMENT	BY APPL	ICANT	Filing Date	02/23/2004		
	Data Suba	nitted: 1/7/	/OE	First Named Inventor	Harry A. ATWATER et al.		
	Date Subr	mued: 1///	<b>105</b>	Group Art Unit	1764		
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Sheet	7	of	7	Attorney Docket Number	047071-0109		

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Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.	τ6
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Examiner Signature	/Shamim Ahmed/ (08/20/2006)	Date Considered	08/20/2006

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup> Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 18 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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	INFORMATIO	ON DISCLO	OSURE	Application Number	10/784,586	5 0005
	STATEMENT	BY APPL	LICANT	Filing Date	02/23/2004	MOA 1 2 5003 S
				First Named Inventor	Harry A. ATWATE	Retal.
				Group Art Unit	1764	To the second
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Sheet	11	of	1	Attorney Docket Number	047071-0109	

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**Examiner Signature** 

/Shamim Ahmed/ (08/20/2006)

**Date Considered** 

08/20/2006

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<sup>&</sup>lt;sup>1</sup> Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Entar Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>8</sup>Applicant is to place a check mark here if English language Translation is attached.

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Date Submitted: 7/24/06

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Application Number	10/784,586				
Filing Date	2/23/2004				
First Named Inventor	Harry A. Jr. ATWATER				
Group Art Unit	1765				
Examiner Name	S. Ahmed				
Attorney Docket Number	047071-0109				

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